

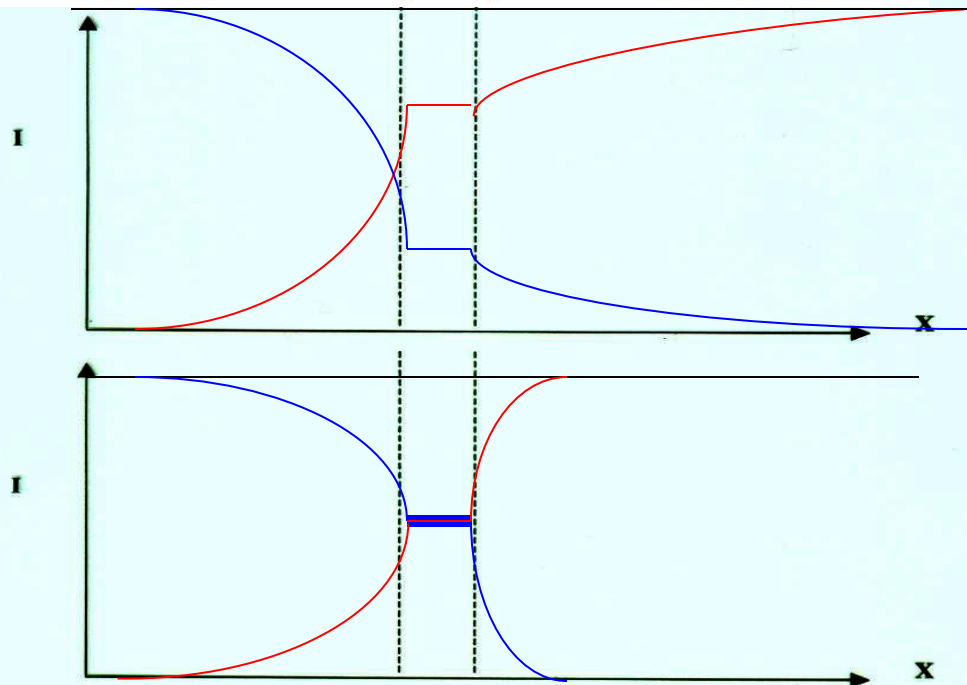
N_a N_d

L_p L_n

N_a N_d

D_p D_n

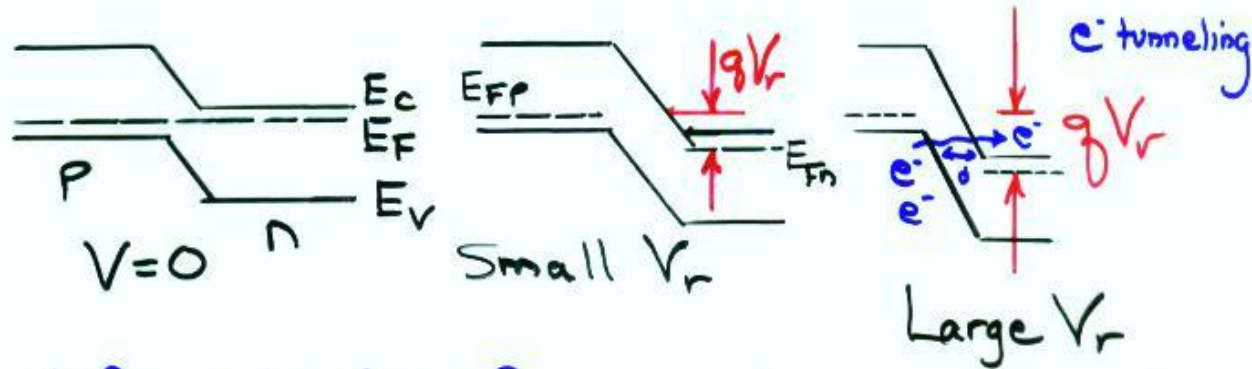
τ_p τ_n



Reverse Field Breakdown

Two Breakdown Mechanisms: \rightarrow Zener
 \rightarrow Avalanche

① Zener



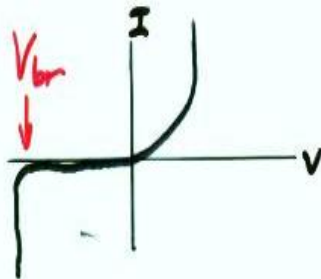
Tunnel Current of e^- from p-side valence band to n-side conduction band.

V_r usually \lesssim a few volts.

$$I \propto |\text{Tunnel Probability}|^2 \propto |P_T|^2$$

$\propto \#e^- \text{ in valence band} \times \# \text{ empty states in conduction band.}$

$$\propto \frac{1}{d}$$



Can think of as "field ionization"
of host atoms at a junction

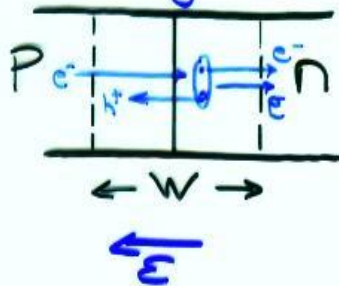
$$E \sim 10^6 \text{ V/cm}$$

V is only a few volts but d is very small.

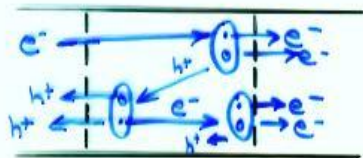
Avalanche Breakdown

For lightly-doped junctions, tunneling negligible.
Instead, impact ionization process.

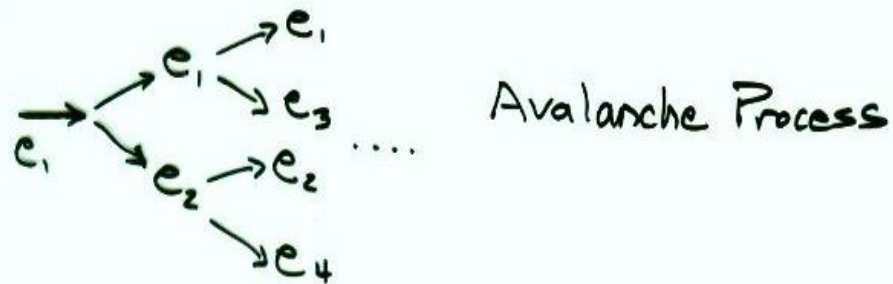
Now, higher voltages and carrier multiplication



Single ionizing collision



Multiple ionizing collisions
primary, secondary, tertiary



Probability of ionizing collision between e^- and lattice = P . ($P < 1$)

$n_{inc} = \#$ of e^- 's incident from $-x_{po}$



$n_{inc} P = \#$ of extra e^- 's after ionizing collision

Total $\#$ after collision = $n_{inc} (1 + P)$

$N_{inc} \cdot P$ secondaries $\rightarrow N_{inc} \cdot P \cdot P$ tertiaries

$$N_{out} = N_{inc} (1 + P + P^2 + P^3 + \dots)$$

Electron multiplication factor

$$M_n = \frac{N_{out}}{N_{in}} = 1 + P + P^2 + P^3 + \dots = \boxed{}$$

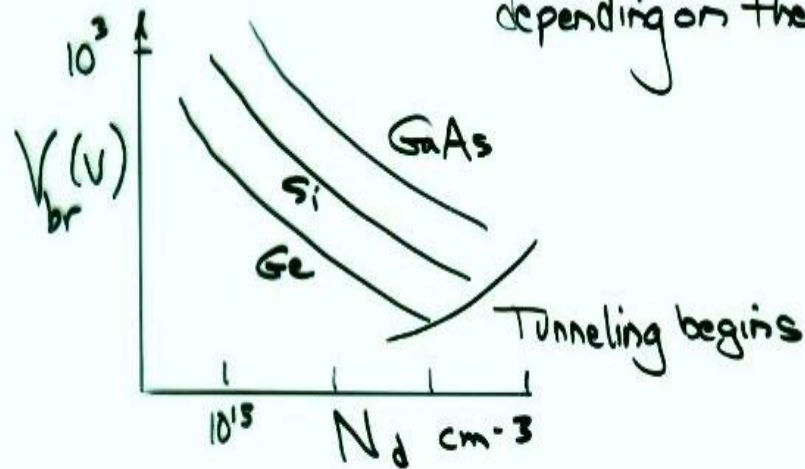
To first order

Expect multiplication to

depend on V_r and doping $\rightarrow E_0 = - \boxed{}$
 $\propto \boxed{}$

$$M = \frac{1}{1 - (V/V_{br})^n} \quad \text{Empirical}$$

n varies from ~ 3 to 6 ,
depending on the junction material



V_{br} increases with band gap E_g since more energy required to ionize electron-hole pairs.

SiC power transistors \rightarrow high breakdown strength. $E_g > 3\text{V}$.

Capacitance of P-N Junctions

Two Types -

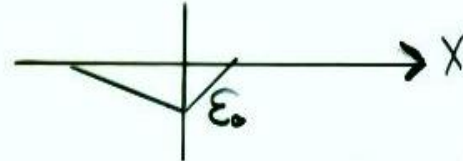
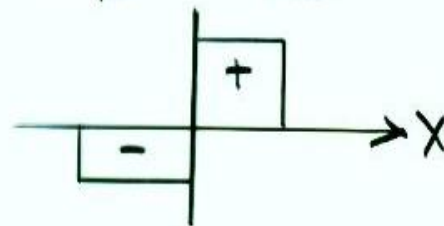
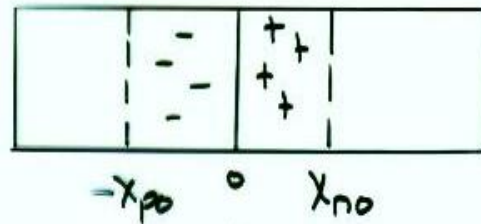
1) Junction C:

- Dipole across W
- Dominant in reverse bias

2) Storage C

- "Diffusion" capacitance: lag of V behind I (Time delay to leave W)
- Dominant in Forward Bias

Both important for time-varying devices.



Charge separation like
parallel-plate capacitor
-| ϵ |

but now

$$C = \frac{Q}{V} \rightarrow C =$$



since Q varies nonlinearly with V .

This nonlinearity useful for some devices,
limiting for other devices.

Non linearity :

$$W = \left[\frac{2\epsilon V_0}{q} \left(\frac{N_A + N_D}{N_A N_D} \right) \right]^{1/2} \quad V=0$$

Equilibrium (5-21)

$$=$$

$V \neq 0$

- W changes with bias, so
uncompensated charge in W changes with V ,
so Q changes with bias.

$$\begin{aligned}
 |Q| &= q A N_d \int_0^{x_{no}} dx = q A N_d x_{no} \text{ (n-side)} \\
 &= q A N_a \int_{-x_{po}}^0 dx = q A N_a x_{po} \text{ (p-side)}
 \end{aligned}$$

Substitute for x_{no} and x_{po} .

$$\begin{aligned}
 W &= x_{no} + x_{po} = x_{po} \left(1 + \frac{x_{no}}{x_{po}} \right) \\
 &= x_{po} (1 + \boxed{})
 \end{aligned}$$

$$x_{no} = \frac{W N_a}{N_a + N_d}$$

$$x_{po} = \frac{W N_d}{N_a + N_d}$$

$$\begin{aligned}
 \text{So } |Q| &= q A N_d N_a W \\
 &\quad \quad \quad (N_d + N_a) \\
 &= q A N_a N_d \left[\frac{z \epsilon (V_0 - V)}{q} \left(\frac{N_a + N_d}{N_a N_d} \right) \right]^{1/2} \\
 &= A \left[z \epsilon q (V_0 - V) \frac{N_a N_d}{(N_a + N_d)} \right]^{1/2}
 \end{aligned}$$

$\left[\dots \right]^{1/2} = W$

Note the $V^{1/2}$ dependence.
 also $(V_0 - V)$ instead of V_0 .

Now take derivative.

$$C_j = \left| \frac{dQ}{d(V_0 - V)} \right| = \frac{A}{z} \left[\boxed{\phantom{\frac{N_a N_d}{N_a + N_d}}} \right]^{1/2}$$

$f = \text{function}$

Voltage-Variable capacitance

Now take derivative.

$$C_j = \left| \frac{dQ}{d(V_0 - V)} \right| = \frac{A}{2} \left[\frac{2\epsilon q}{(V_0 - V)} \frac{N_a N_d}{(N_a + N_d)} \right]^{1/2}$$

j = junction

Voltage-Variable capacitance

$$\frac{1}{V^{1/2}}, \text{ not } \frac{1}{V}$$

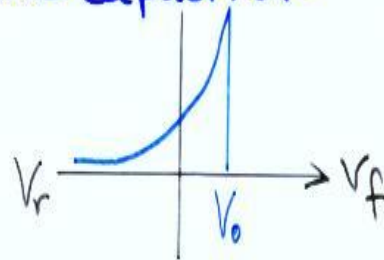
p-n junction device using voltage-variable capacitance is "Varactor"

C_j has analogous form to parallel plate capacitor:

$$C_j = \epsilon A \left[\frac{q}{2\epsilon(V_0 - V)} \frac{N_a N_d}{(N_a + N_d)} \right]^{1/2} = \boxed{}$$

W corresponds to plate separation
of parallel plate capacitor

Big difference:



Not constant

Asymmetric Junctions

W is primarily in



C is determined by only one doping concentration.

$$X_{po} N_a =$$



Example: p^+-n $N_a \gg N_d$

so $x_{n0} \gg x_{p0}$

$x_{n0} \approx W$, $x_{p0} \approx 0$

$$C_j = \frac{A}{2} \left[\frac{2\epsilon\epsilon_0}{(V_0 - V)} \frac{N_a N_d}{(N_a + N_d)} \right]^{1/2}$$

$$= \frac{A}{2} \left[\frac{2\epsilon\epsilon_0}{(V_0 - V)} N_d \right]^{1/2}$$

(and vice-versa if dopings are reversed)

Can get N by measuring C_j (assuming sharp step)